Shaolin Zhou

List of Publications by Year
in descending order

Source: https://exaly.com/author-pdf/11485901/publications.pdf

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23	253	1040056	940533
papers	citations	9	16
		h-index	g-index

23	23	23	110
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Phase Change Metasurfaces by Continuous or Quasi-Continuous Atoms for Active Optoelectronic Integration. Materials, 2021, 14, 1272.	2.9	6
2	Catenary-based phase change metasurfaces for mid-infrared switchable wavefront control. Optics Express, 2021, 29, 23006.	3.4	10
3	Phase-Change Metasurface by U-Shaped Atoms for Photonic Switch with High Contrast Ratio. Coatings, 2021, 11, 1499.	2.6	4
4	Bistable active spectral tuning of one-dimensional nanophotonic crystal by phase change. Optics Express, 2020, 28, 8341.	3.4	7
5	Phase change induced active metasurface devices for dynamic wavefront control. Journal Physics D: Applied Physics, 2020, 53, 204001.	2.8	13
6	Phase Change Memory Cell With Reconfigured Electrode for Lower RESET Voltage. IEEE Journal of the Electron Devices Society, 2019, 7, 1072-1079.	2.1	4
7	Prototyping of Terahertz Metasurface by One-Step Lithographically Defined Templating. IEEE Photonics Technology Letters, 2018, 30, 971-974.	2.5	2
8	The Anomaly of Periodicity Doubling in Projection Photolithography of Periodic Features. IEEE Photonics Technology Letters, 2016, 28, 2529-2532.	2.5	0
9	Effect of Near-Field Diffraction in Photolithography of Hexagonal Arrays for Dichroic Filters. IEEE Photonics Journal, 2016, 8, 1-11.	2.0	0
10	UV spectrum-integral Talbot lithography for amplitude periodic micro-grating fabrication. , 2016, , .		0
11	Spectrum-Integral Talbot Effect for UV Photolithography With Extended DOF. IEEE Photonics Technology Letters, 2015, 27, 2201-2204.	2.5	6
12	MoirÃ© fringe alignment using composite circular-line gratings for proximity lithography. Optics Express, 2015, 23, 20905.	3.4	18
13	Scalar-Based Analysis of Phase Gratings Etched in the Micro/nanofabrication Process. IEEE Photonics Journal, 2015, 7, 1-11.	2.0	1
14	MoirÃ© interferometry with high alignment resolution in proximity lithographic process. Applied Optics, 2014, 53, 951.	1.8	8
15	The leveling of mask and wafer in proximity nanolithography using fringe pattern phase analysis. Optik, 2014, 125, 3176-3180.	2.9	0
16	MoirÃ©-Based Phase Imaging for Sensing and Adjustment of In-Plane Twist Angle. IEEE Photonics Technology Letters, 2013, 25, 1847-1850.	2.5	12
17	Influence of tilt moirÃ© fringe on alignment accuracy in proximity lithography. Optics and Lasers in Engineering, 2013, 51, 371-381.	3.8	24
18	Four-quadrant gratings moirÃ© fringe alignment measurement in proximity lithography. Optics Express, 2013, 21, 3463.	3.4	26

#	Article	IF	Citations
19	Positioning scheme based on grating modulation and phase imaging in lithography. , 2010, , .		1
20	Extended dual-grating alignment method for optical projection lithography. Applied Optics, 2010, 49, 708.	2.1	11
21	MoirÃ©-based focusing and leveling scheme for optical projection lithography. Applied Optics, 2010, 49, 5959.	2.1	13
22	Tilt-modulated spatial phase imaging method for wafer-mask leveling in proximity lithography. Optics Letters, 2010, 35, 3132.	3.3	25
23	Fourier-based analysis of moirÃ© fringe patterns of superposed gratings in alignment of nanolithography. Optics Express, 2008, 16, 7869.	3.4	62